

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S29	2031	Photoresist same Particles	USPAT	SAME	OFF	2006/03/09 16:44
S30	350911	TiO2 or Silica or Polystyrene	USPAT	OR	OFF	2006/03/09 16:45
S31	85	S29 same S30	USPAT	SAME	OFF	2006/03/09 16:46
S32	276733	photoresist or resist or photosensitive	USPAT	OR	OFF	2006/03/13 14:24
S33	5188	mask same particles	USPAT	SAME	OFF	2006/03/13 14:25
S35	2698	S32 and S33	USPAT	AND	OFF	2006/03/13 14:35
S36	610459	TiO2 or titanium dioxide or silica or polystyrene	USPAT	OR	OFF	2006/03/13 14:33
S37	2235	S36 and S33	USPAT	OR	OFF	2006/03/13 14:36
S38	1289	S37 and S35	USPAT	OR	OFF	2006/03/13 14:34
S39	1167	S32 same S33	USPAT	SAME	OFF	2006/03/13 14:35
S40	348	S36 same S33	USPAT	SAME	OFF	2006/03/13 14:36
S41	79	S39 same S40	USPAT	SAME	OFF	2006/03/13 14:37
S42	91	S39 and S40	USPAT	AND	OFF	2006/03/22 16:22
S43	1184	430/396.ccls.	USPAT	OR	OFF	2006/03/16 09:08

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	321483	passivation or protective	USPAT	OR	OFF	2006/03/22 13:28
L2	393143	polyacrylates or polycarbonate or polyethylene terephthalate or polyethylene	USPAT	OR	OFF	2006/03/22 13:32
L3	14378	L1 same L2	USPAT	SAME	OFF	2006/03/22 13:32
L4	217686	photoresist or resist	USPAT	OR	OFF	2006/03/22 13:33
L5	1853	L3 and L4	USPAT	AND	OFF	2006/03/22 13:33